

Title (en)  
PLASMA PROCESSING APPARATUS

Title (de)  
PLASMA-BEHANDLUNGSVORRICHTUNG

Title (fr)  
APPAREIL DE TRAITEMENT PAR PLASMA

Publication  
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Application  
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Abstract (en)  
[origin: WO9966531A1] There is disclosed a plasma processing apparatus comprising: a) a chamber having a plasma containing region, the chamber having a dielectric portion; b) an antenna (6) for coupling radio frequency (RF) power into the plasma; and c) a shield member (2) which reduces the level of RF power capacitively coupled into the plasma, wherein the shield member (2) comprises a conducting portion and is positioned between the plasma and the dielectric portion. Also disclosed is a shield member, particularly one for use in the described plasma processing apparatus.

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